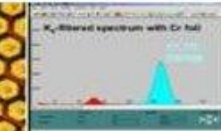
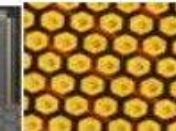
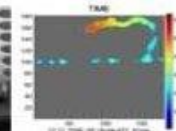
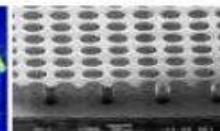
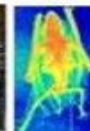


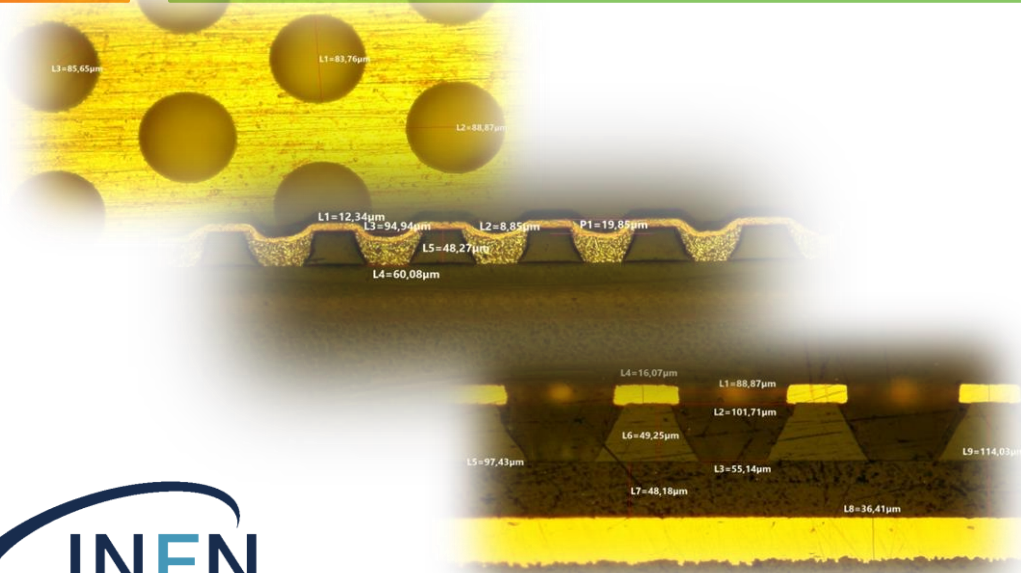


RD51 Collaboration



The micro-RWELL for R1/R2

Status & plans



G. Bencivenni

On behalf of DDG - LNF



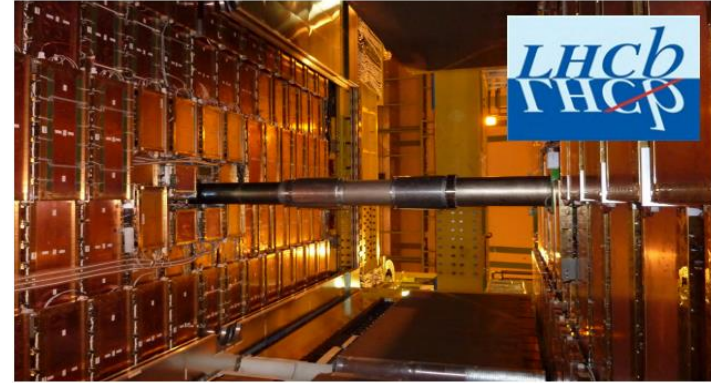
LHCb Italia meeting - 15 Nov 2022



LHCb upgrade II (Run5 – Run6)

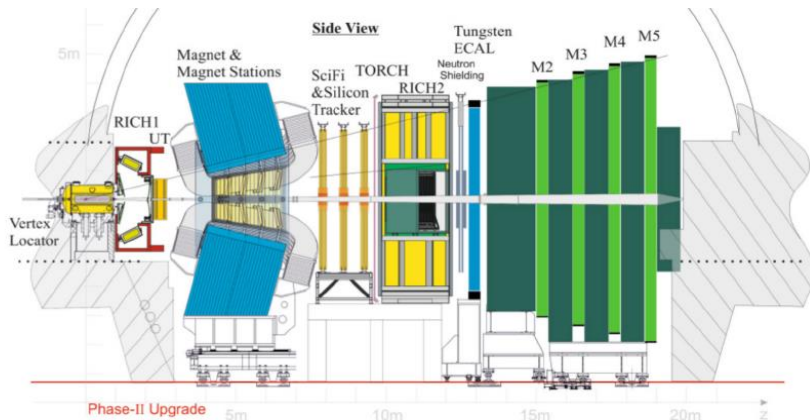
LHCb muon apparatus Run5 – Run6 option detector requirements

- Rate up to **1 MHz/cm²** on detector single gap
- Rate up to **700 kHz** per electronic channel
- Efficiency quadrigap $\geq 99\%$ within a BX (25 ns)
- Stability up to **1C/cm²** accumulated charge in 10y at M2R1, G=4000



Detector size & quantity (4 gaps/chamber - redundancy)

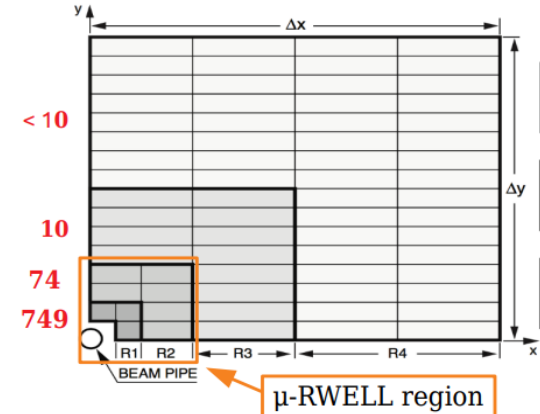
- **R1÷R2: 576 detectors, size 30x25 to 74x31 cm², 90 m² detector (130 m² DLC)**
- ~~R3: 768 detectors, size 120x25 to 149x31 cm², 290m²-det.~~
- ~~R4: 3072 detectors, size 120x25 to 149x31 cm², 1164 m²-det.~~



Rates (kHz/cm ²)	M2	M3	M4	M5
R1	749	431	158	134
R2	74	54	23	15
R3	10	6	4	3
R4	8	2	2	2

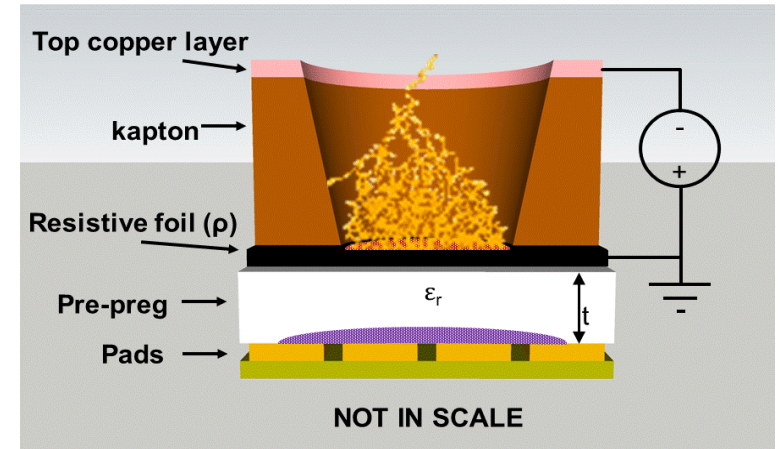
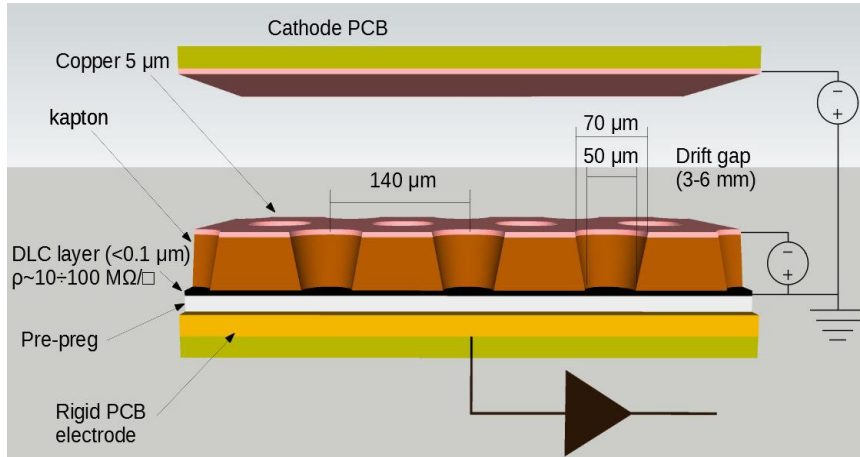
Area (m ²)	M2	M3	M4	M5
R1	0.9	1.0	1.2	1.4
R2	3.6	4.2	4.9	5.5
R3	14.4	16.8	19.3	22.2
R4	57.6	67.4	77.4	88.7

M2 station - max rate (kHz/cm²)



The μ -RWELL (reminder)

G. Bencivenni et al., *The micro-Resistive WELL detector: a compact spark-protected single amplification-stage MPGD*, 2015 JINST 10 P02008



The μ -RWELL is a **resistive MPGD** composed of two elements:

- **Cathode**
- **μ -RWELL_PCB:**
 - a **WELL** patterned **kapton foil (w/Cu-layer on top)** acting as **amplification stage**
 - a **resistive DLC layer**(*) w/ $\rho \sim 10 \div 100 \text{ M}\Omega/\square$
 - a standard **readout PCB** with **pad/strip** segmentation

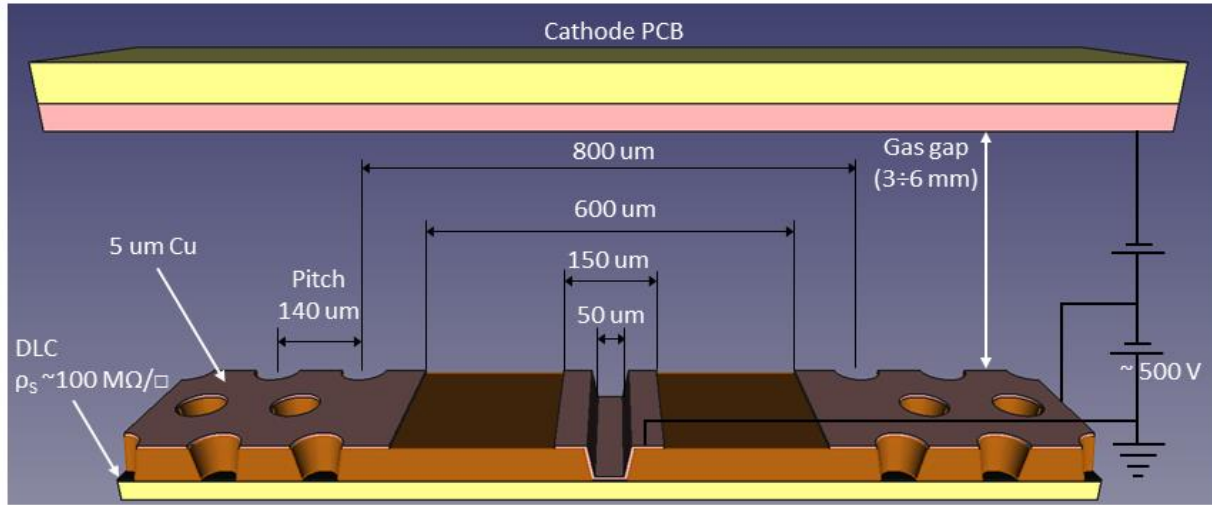
(*) DLC foils are currently provided by the Japan Company – BeSputter

The “**WELL**” acts as a **multiplication channel** for the ionization produced in the drift gas gap.

The **resistive stage** ensures the **spark amplitude quenching**.

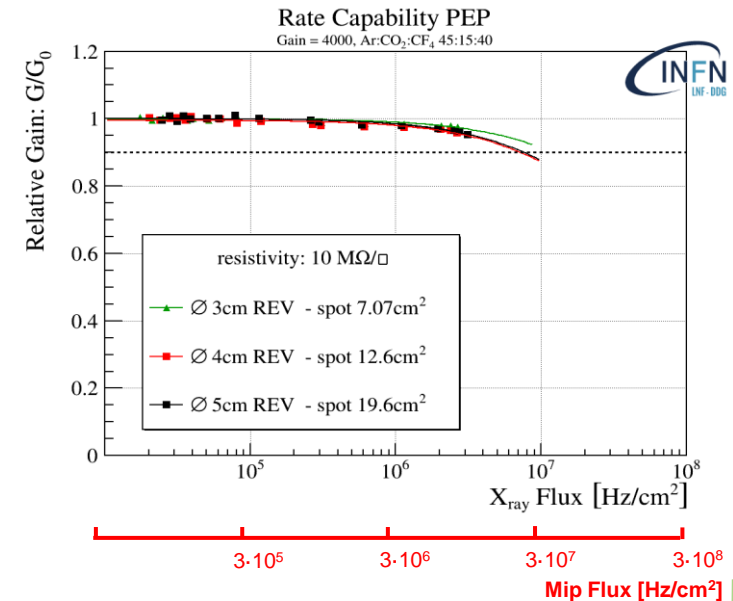
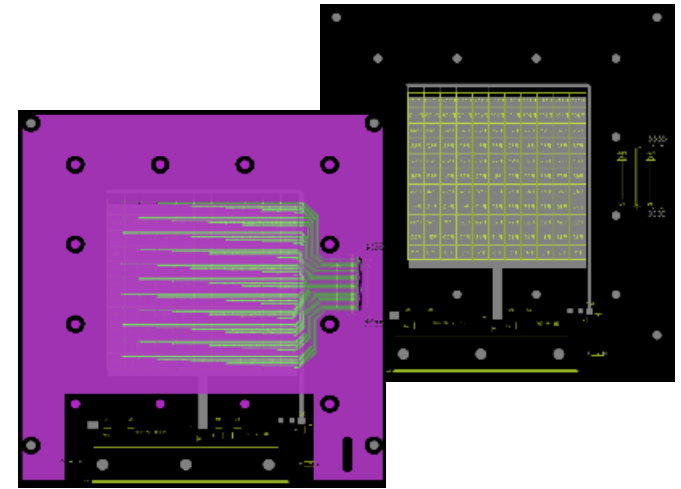
Drawback: capability to stand high particle fluxes reduced, but **largely recovered** with appropriate **grounding schemes** of the **resistive layer**

The HR layout



The **PEP** layout (Patterning – Etching – Plating) is the **state of art** of the **high rate** layout of the μ -RWELL developed for **LHCb**

- **Single DLC** layer
- **Grounding line from top** by kapton etching and plating (pitch down to 1/cm)
- **No alignment** problems
- **High rate** capability
- **Scalable to large size** (up to 1.2x0.5 m for the upgrade of CLAS12)



QA & QC

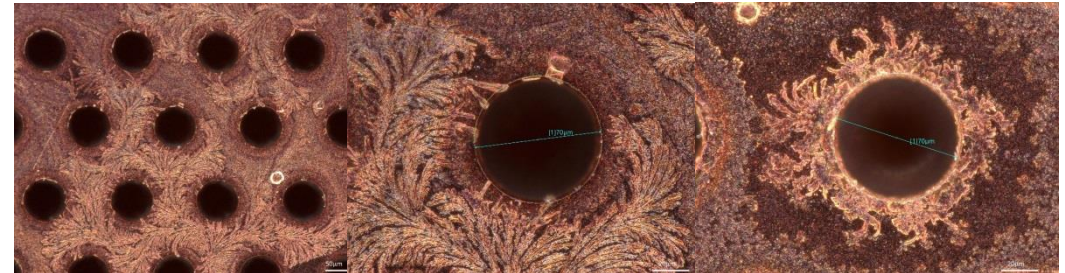
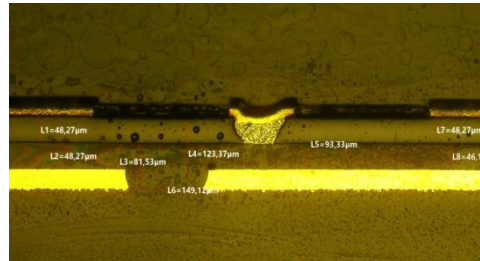
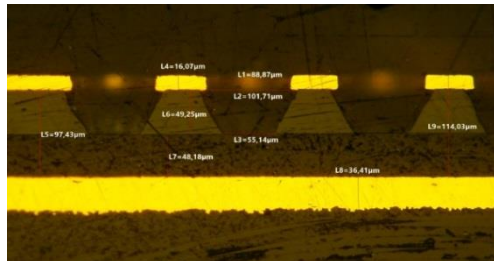
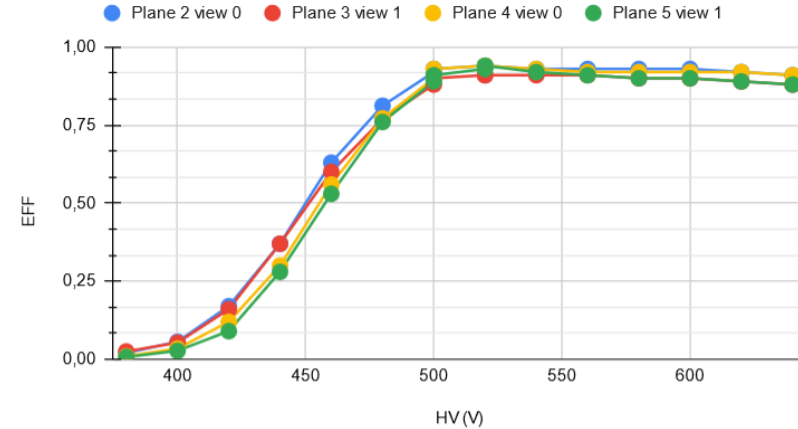


The technology (based on **SBU** layout) has been **largely improved** in the last year, thanks to the introduction of the “**dry-electrical-cleaning**”, a sort of a hot HV conditioning leading to a soft clean of the residual imperfections of the detector manufacturing.

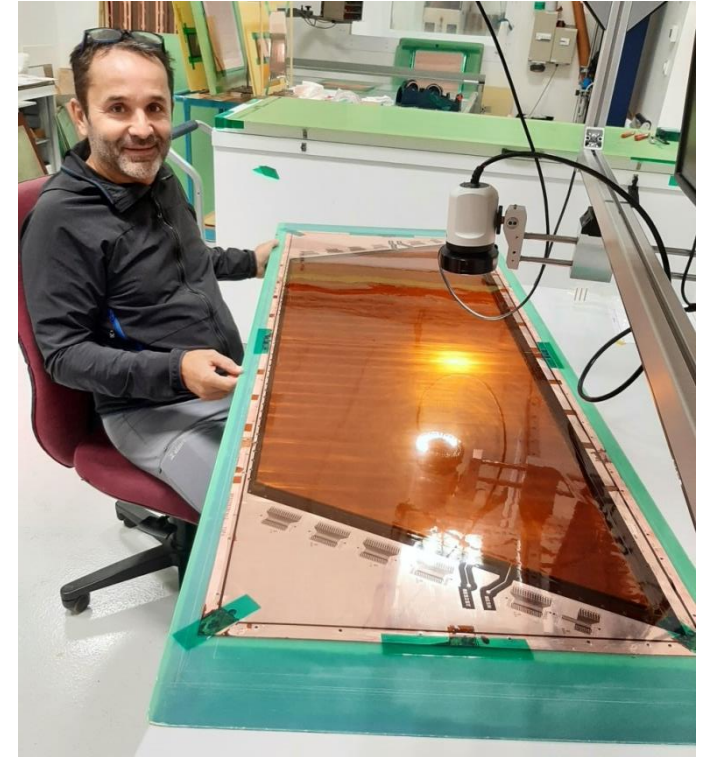
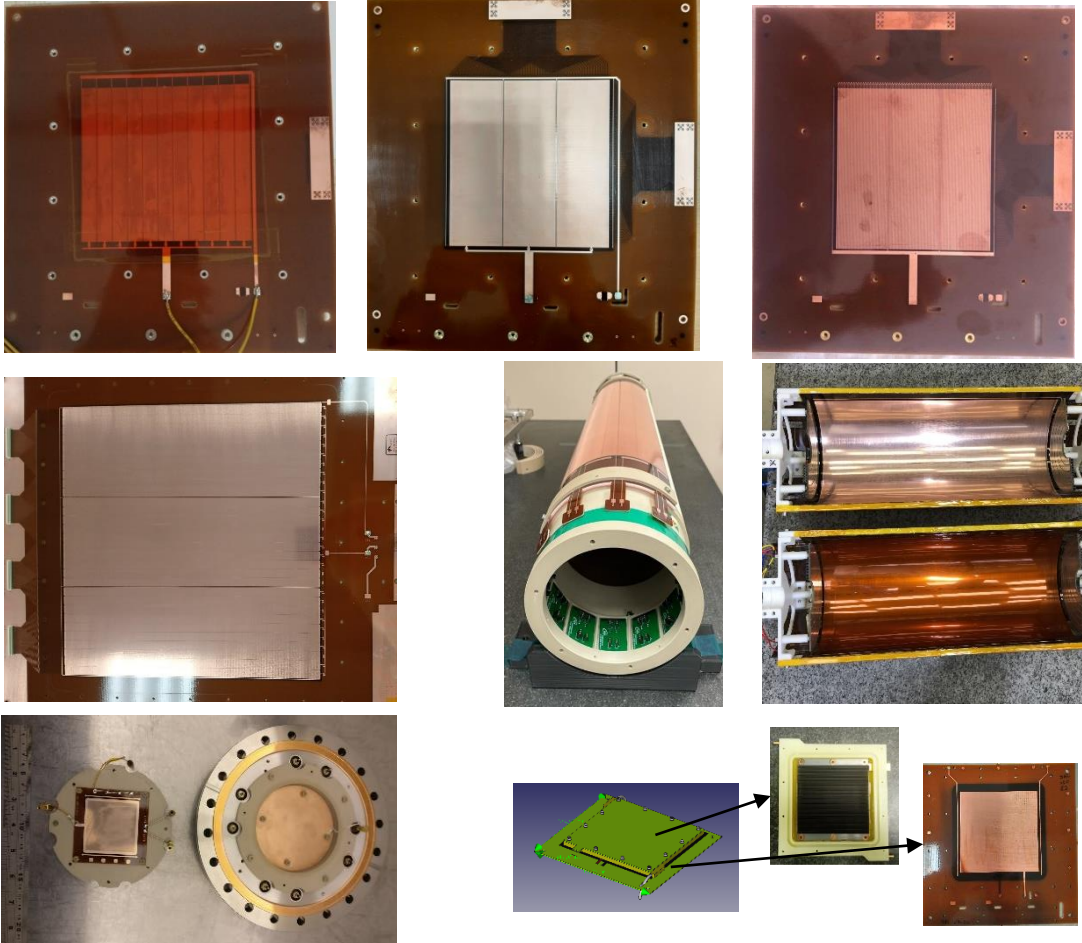
Detector stability improved → up to **200V** large plateau, **estimated gain up to $4\div 5 \times 10^4$** (to be measured).

Optical metallographic survey (in ELTOS) as well as **SEM analysis** (at CERN) are used to take all construction steps under control as well as checking effects for possible aging/etching (by fluorine ...).

Very preliminary



Technology spread



The improvement of the quality and yield is a clear **by-product** of the **technology spread** (in particular CLAS12 upgrade at JLAB).

Test facilities and synergies

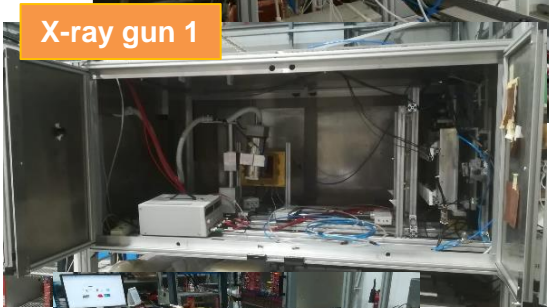
X-ray setup @ LNF



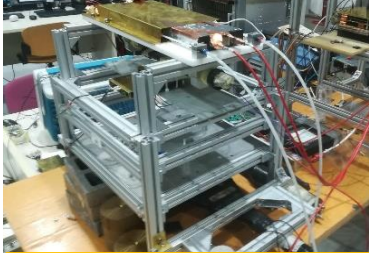
X-ray gun 2



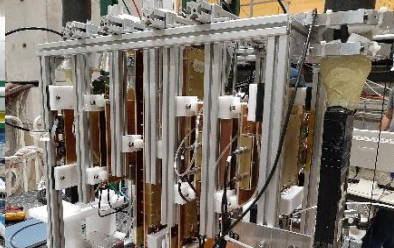
X-ray gun 1



Cosmic ray setup @ LNF

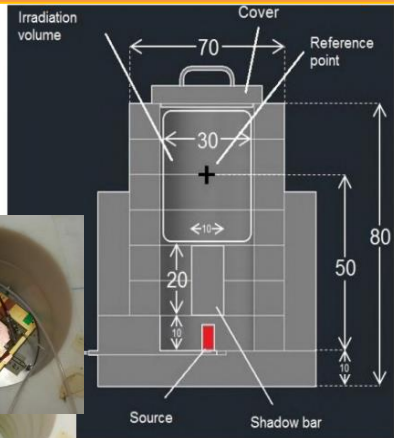


CERN – SpS H8C



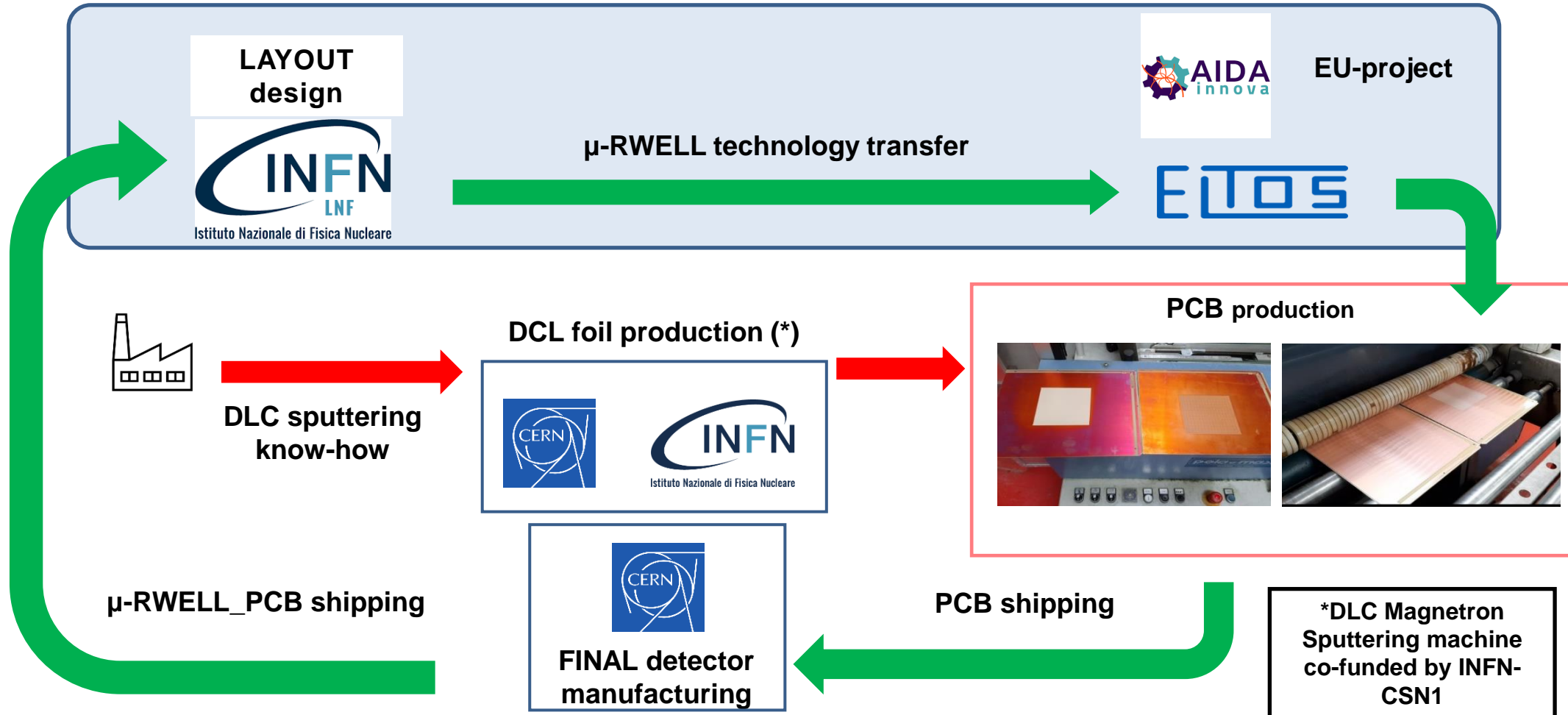
ENEA HOTNES thermal neutron facility

PSI – π -M1



Several **test facilities** in Frascati (LNF/ENEA), CERN (H8C) and PSI (PiM1) are exploited for detectors characterization. **Synergies** with external groups (Ferrara, Bologna, RM2-CLAS12) gave an important boost to the technology. For sure the involvement of other LHCb-Muon groups would be desirable in the near future, in particular in view of the phase of major commitment for the integration tests.

Technology transfer (I)



Technology transfer (II)

Step 0 - Detector PCB design @ LNF

Step 1 - CERN_INFN DLC sputtering machine @ CERN

- Installed and commissioned beginning of Nov 2022
- Operated by CERN + LNF (& INFN) staff

Step 2 - Producing readout PCB by ELTOS

- pad/strip readout

Step 3 - DLC patterning by ELTOS

- photo-resist ⊕ patterning with BRUSHING-machine

Step 4 - DLC foil gluing on PCB by ELTOS

- double 106-prepreg ~2x50μm thick
- PCB planarizing w/ screen printed epoxy ⊕ single 106-prepreg

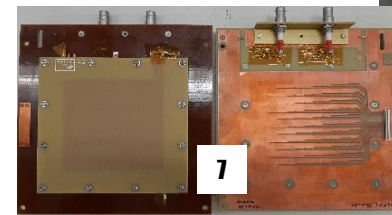
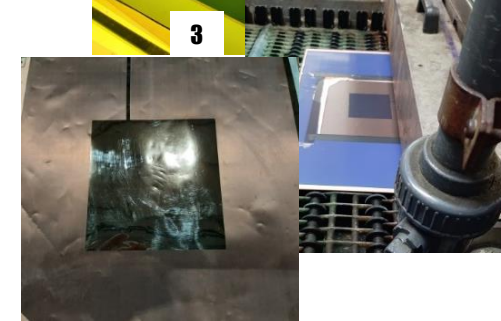
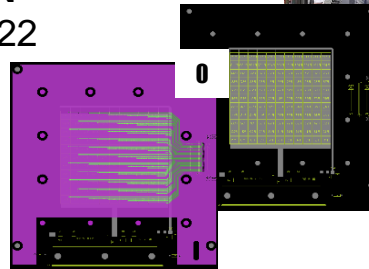
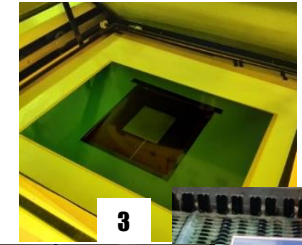
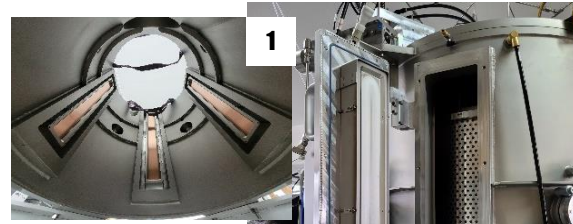
Step 5 - Top copper patterning by CERN (in future by ELTOS)

- Holes image and HV connections by Cu etching

Step 6 - Amplification stage patterning by CERN

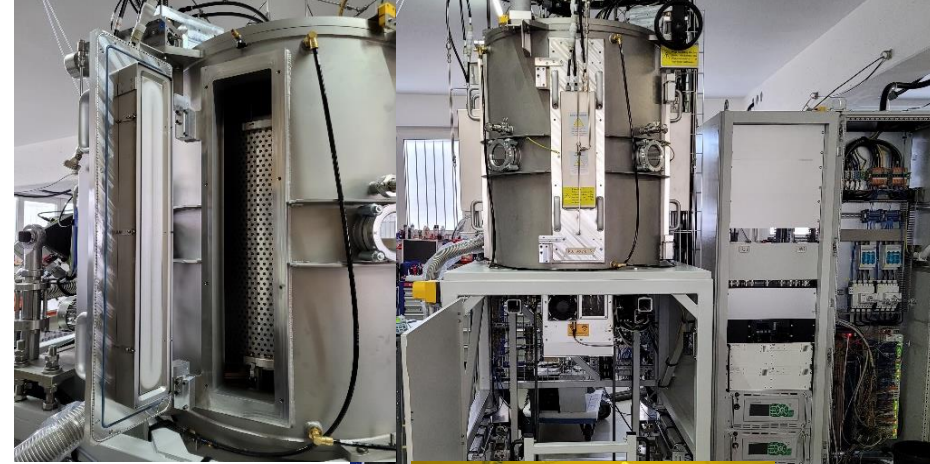
- PI etching ⊕ plating ⊕ ampl-holes

Step 7 – Final electrical cleaning and detector closing @ CERN



CID: the CERN-INFN DLC machine

- **Flexible substrates, coating areas up to 1.7 m × 0.6 m**
 - **Rigid substrates, coating areas up to 0.2 m × 0.6 m**
 - **Five cooled target holders, arranged as two pairs face to face and one on the front, equipped with five shutters**
 - **Sputtering & co-sputtering different materials, in order to create a coating layer by layer or an adjustable gradient in the coating**
-
- **Installation, week 43**
 - **Commissioning & training of the CERN-INFN teams, week 44**
 - **Next test-phase, week 47**
 - **1 week/month joint CERN-INFN test runs**



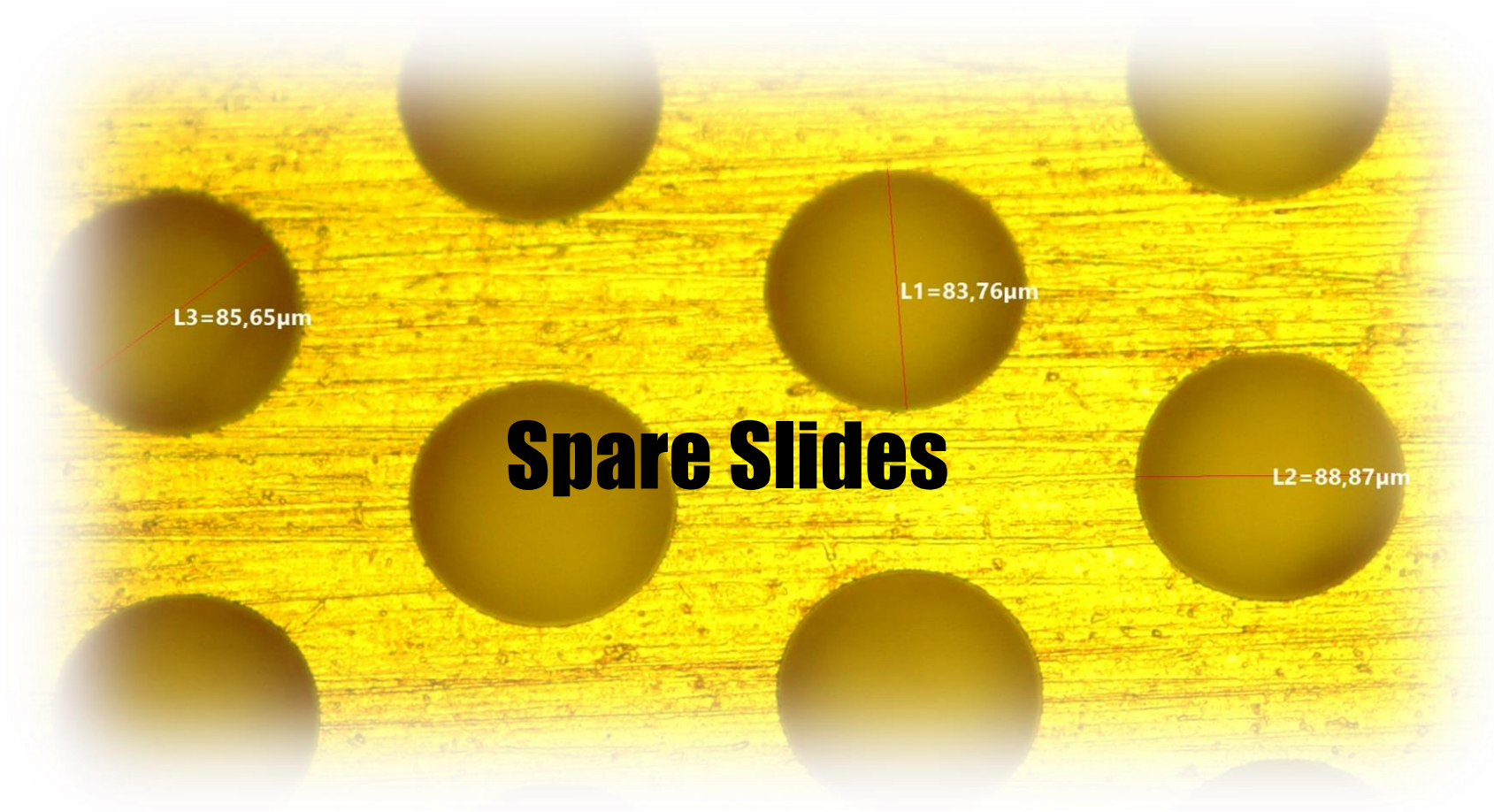
Summary & Outlook

The advances in the **μ -RWELL technology** during the last two years lead to **large improvements in terms of stability and production yield**

- The challenge for the next two years is the **TT of resistive-MPGD** to the PCB industry (ELTOS)
- **Key-point** is the acquisition of the **DLC magnetron sputtering machine co-funded by CERN and INFN** that is going in operation in these days

Mid-term To Do List:

- **Integration with the electronics (FATIC)** developed by **Bari** group, with the goal of a better understanding of the **requirements for a new dedicated ASIC**
 - **Test-bench** in Bari within the **end of the 2022**
 - **cosmic ray stand** within **spring 2023**
 - **Test beam** (eff in 25 ns, OR/maj..etc vs gas mix) within **summer 2023**
- **Optimization** of the **PEP** layout & design of the **M2R1/R2 proto-0** → **2023/24**
- **Global irradiation** (LNF X-ray tube, GIF++ w/Gas CERN group) → **2023/2024**
- **Eco-gas fast** mixtures (???)



L3=85,65µm

L1=83,76µm

L2=88,87µm

Spare Slides

Tentative schedule

	2022	2023	2024	2025	2026	2027	2028	2029	2030	2031	2032	2033	2034	
	RUN3				LS3				RUN4				LS4	
new HR layout design & test (w/X-ray)	■	■												
eco-gas searches		■	■											
CR/test beam with HR proto		■												
global irradiation test (GIF++ ?)		■	■											
finalizing design HR layout		■												
proto-0 construction & test			■	■										
TDR				■	■									
preparation mass production (ELTOS+ CERN)					■	■								
DLC production w/CID						■				■				
R1 - Production/test						■	■	■	■					
R2-M2/M3 - production/test								■	■	■				
R2-M4/M5 - production/test										■	■	■	■	
Installation/commissioning (?)												■	■	

La costruzione segue i seguenti step(*):

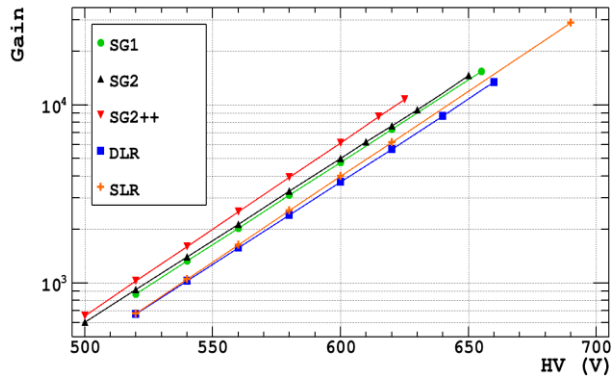
- CERN → produzione DLC con macchina sputtering CID
- Eltos → PCB, DLC patterning & gluing
- CERN → finalizzazione rivelatore con etching kapton (RUI)
- CERN → assemblaggio con frame e catodi e procedura di conditioning (RUI)
- CERN → test finale rivelatori e integrazione elettronica (personale INFN)

(*) tempi e modalità di produzione definite con Rui & Eltos e considerando un solo «integration group»

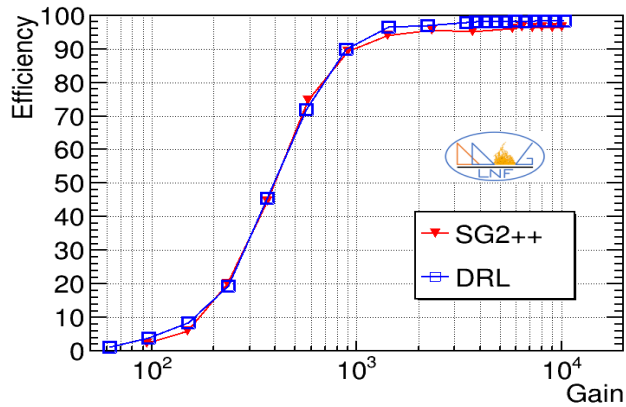
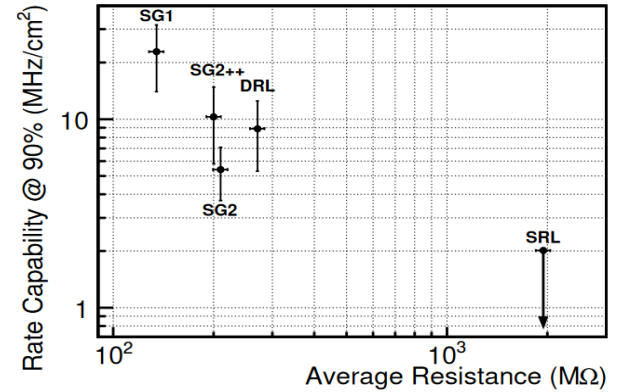
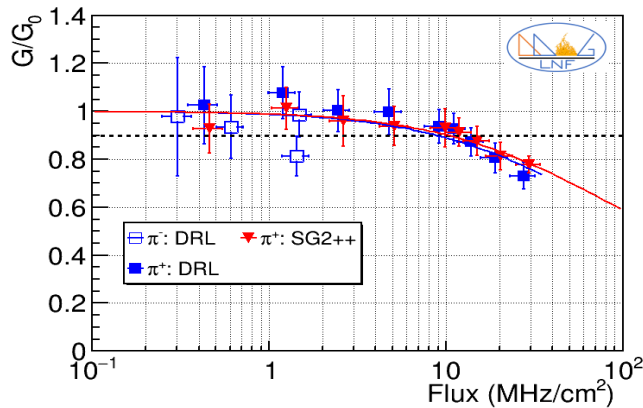


High-rate layouts performance w/m.i.p.

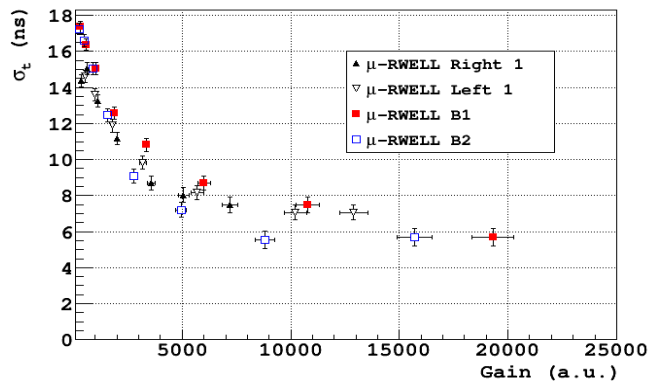
Gain up to $\sim 10^4$



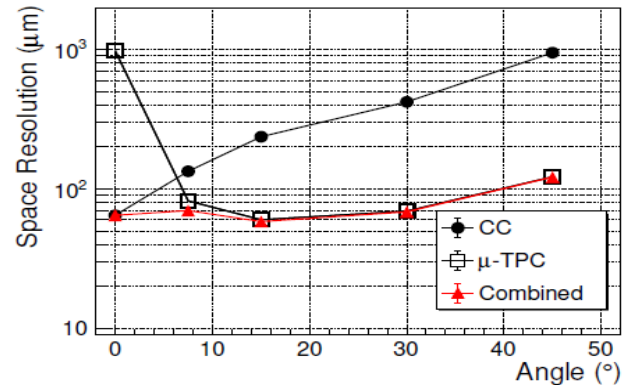
Rate capability up to 10–20 MHz/cm²



Efficiency $\sim 97\%$



Time resolution 5-6 ns



Space resolution down to 60 μm